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AMENDMENTS TO THE CLAIMS

Please amend claim 1 as follows.

Please cancel claims 2 and 5 without prejudice.

1. (Currently amended) A method, comprising:
lithographically patterning a corner over a material;
~~selectively removing anisotropically etching~~ portions of the material based on the
lithographic pattern to obtain a region of the material that defines the corner; and
~~further removing isotropically etching additional~~ portions of the material from the
region of the material to sharpen the corner.
2. (Cancelled)
3. (Original) The method of claim 1 wherein lithographically patterning the corner
includes applying a photoresist material.
4. (Original) The method of claim 3, further comprising removing the photoresist
material from selected areas prior to sharpening the corner.
5. (Cancelled)
6. (Original) The method of claim 1 wherein the material comprises a first material, the
method further comprising:
placing a second material in the region; and
removing excess second material from areas outside of the region.